

Title (en)

ANODIC BONDING METHOD AND APPARATUS FOR X-RAY MASKS

Publication

EP 0153096 B1 19900207 (EN)

Application

EP 85300817 A 19850207

Priority

US 58060084 A 19840216

Abstract (en)

[origin: EP0153096A2] @ A structure for use in a X-ray membrane (pellicle) mask is provided in which anodic bonding of layers is employed. Anodic bonding as used here provides a permanent bond between the layers, has zero thickness and provides substantial improvements in the obtained flatness of the mask by eliminating conventional glue for attachment. By applying a voltage between a layer, such as silicon, and a glass plate, and simultaneously heating both elements a permanent bond is established which is extremely flat thus providing minimum misalignment of the mask during subsequent X-ray lithography fabrication.

IPC 1-7

G03F 1/00

IPC 8 full level

G03F 1/22 (2012.01); **H01L 21/027** (2006.01)

CPC (source: EP US)

G03F 1/22 (2013.01 - EP US); **Y10T 428/265** (2015.01 - EP US)

Cited by

EP1462422A3; US9640514B1

Designated contracting state (EPC)

DE FR GB NL

DOCDB simple family (publication)

EP 0153096 A2 19850828; **EP 0153096 A3 19851204**; **EP 0153096 B1 19900207**; DE 3576003 D1 19900315; JP H0466096 B2 19921022; JP S60186840 A 19850924; US 4632871 A 19861230

DOCDB simple family (application)

EP 85300817 A 19850207; DE 3576003 T 19850207; JP 2209885 A 19850208; US 58060084 A 19840216